## **Supporting Information for**

## Noise and Sensitivity Characteristics of Solid-State Nanopores with a Boron

## Nitride 2-D Membrane on a Pyrex Substrate

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## Supporting information

	Туре	Dimension	Supporting layer	A <sub>N</sub> , Noise power
	Graphene	Φ 8 nm / 3 ~ 15 layer	$\Phi$ 1.5 $\mu$ m window	$7 \times 10^{-6}$
Nano.lett., 2010	Graphene with	Φ 7.5 nm /	/	$2.5 \times 10^{-7}$
	TiO2	Gr with $TiO_2 5 nm$	SiN 40 nm	
Ashvani et.al.,			Φ 60 ~ 80 nm	
Nanotechnology,	Graphene	Φ 5 nm / few layers (1~3 nm)	window/	$6.7 \times 10^{-7}$
2013			SiN 20 nm	
Dekker <i>et.al.,</i>			Φ1μm window /	6
Nanotechnology,	Graphene	Φ 10 nm / single layer	SiN 200 nm	$6.3 \times 10^{-6}$
2015				
Zhi et al Scientific			200 x 200 nm	
	BN	Φ 10 nm / 1~2 layer	window/	$6.7 \times 10^{-7}$
Reports, 2013			SiN 50 nm	
Our results	BN	Φ 4 nm / single layer	gle layer $\Phi$ 60~ 80 nm w layers w layers SiN 100 nm w layers	$1.3 \times 10^{-6}$
		Φ 4 nm / few layers		$7.6 \times 10^{-7}$
		$\Phi$ 8 nm / few layers		$3.7 \times 10^{-8}$
		Φ 12 nm / few layers		$2.1 \times 10^{-8}$

**Table S1.** Noise powers values compared with the reported 2-D nanopores.



**Figure S1.** Power spectral densities of  $\Phi$  4 nm (25 nS), 8 nm (78 nS), 12 nm (113 nS) *m*-BN nanopores in 1 M KCl with 1x TE buffer (pH 8.0) at 100 mV. Blue solid lines are noise fits of  $S(f) = A/f^{\beta}$  (where A is fitting parameter and  $0 < \beta < 2$ ).



**Figure S2.** (a) Ionic current traces for 1kbp dsDNA translocation at 150 mV (black), 200 mV (red) and 250 mV (blue) through  $\Phi$  4 nm *m*-BN nanopore in 1M KCl with TE buffer (pH 8.0), filtered at 10 kHz. Each trace is measured during 10 sec. (b) Scatter plots of blockade current ( $\Delta$ I) and dwell time for 150 mV, 200 mV and 250 mV. (c) Normalized histogram of  $\Delta$ I corresponding to (b) with different voltages. The inset is blockade current level as a function of voltage, showing linear dependency of  $\Delta$ I on the applied voltage.



**Figure S3.** (a) Histogram of current drops, which magnitude is larger than  $10 \times I_{RMS}$ , at 200mV and 100 kHz. The dotted lines are fitted to Gaussian distributions and each distribution is divided to 'bouncing' and 'translocation', respectively. Inset shows a magnified view of representative bouncing and translocation events. (b) Mean  $\Delta I$  and  $t_d$  values of translocation events and bouncing spikes as a function of voltage.



**Figure S4.** (a) Ionic current traces for 1 kbp dsDNA translocation through  $\Phi$  4 nm *m*-BN pore at 150 mV applied voltage, filtered at 100 kHz (blue) and 10kHz (red) in 1 M KCl with TE buffer (pH 8.0). (b) A magnified view of 7 DNA translocation events with different durations ranged from 20 and 200 us.



**Figure S5.** Signal to noise ratio of  $\Phi$  4 nm *m*-BN nanopore as a function of voltages at 10 kHz and 100 kHz; SNR =  $\Delta I / I_{RMS}$ .